



Ultraviolet Semiconductor Materials for Next-Generation Water Security



Mary H. Crawford

Sandia National Labs

Semiconductor Material and Device Sciences Dept.
Org. 01123

Acknowledgements: *A. A. Allerman, A. M. Armstrong, M. A. Miller,
J. J. Wierer, N. A. Modine and A.F. Wright*



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Water Security



Key Aspect: Robust water quality assurance
(*terrorist attacks, natural disasters, etc*)

Potential Strategy:

Supplement centralized water treatment facilities with distributed point-of-entry (POE) and point-of-use (POU) systems*

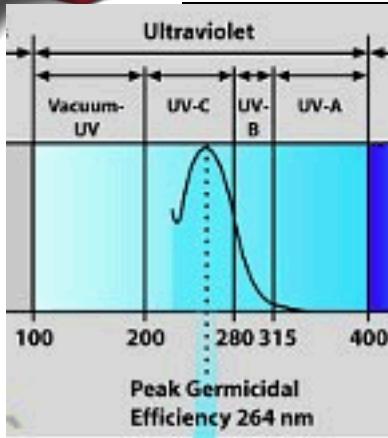
Desired Attributes:

- broadly effective (*biological, chemical*)
- high reliability, low maintenance
- low cost, low energy consumption
- low environmental impact (*manufacture, use, disposal*)

Attributes for New Functionality:

- no power requirements or solar-powered
- “smart” integration of sensing and purification functions
- communication between networked POE/POU systems

Next-Generation UV Sources for Water Purification



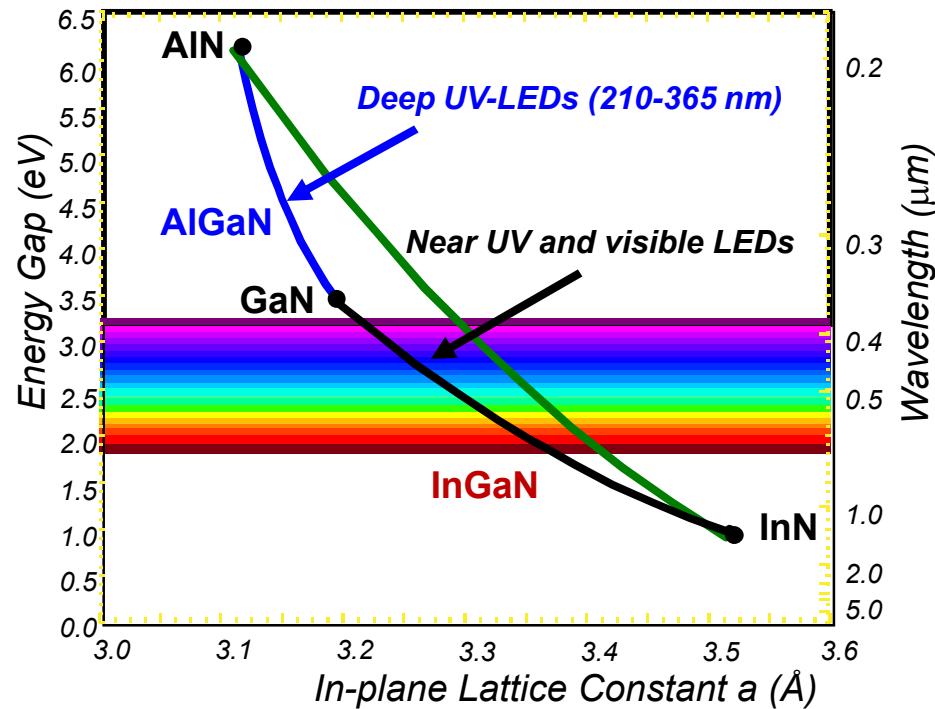
UV LED Advantages:

- Avoids hazards of Hg disposal
- Integration with control electronics
- Low power /solar power
- Instant turn-on
- Wavelength tunable (340 nm /265 nm for fluorescence sensing/purification)

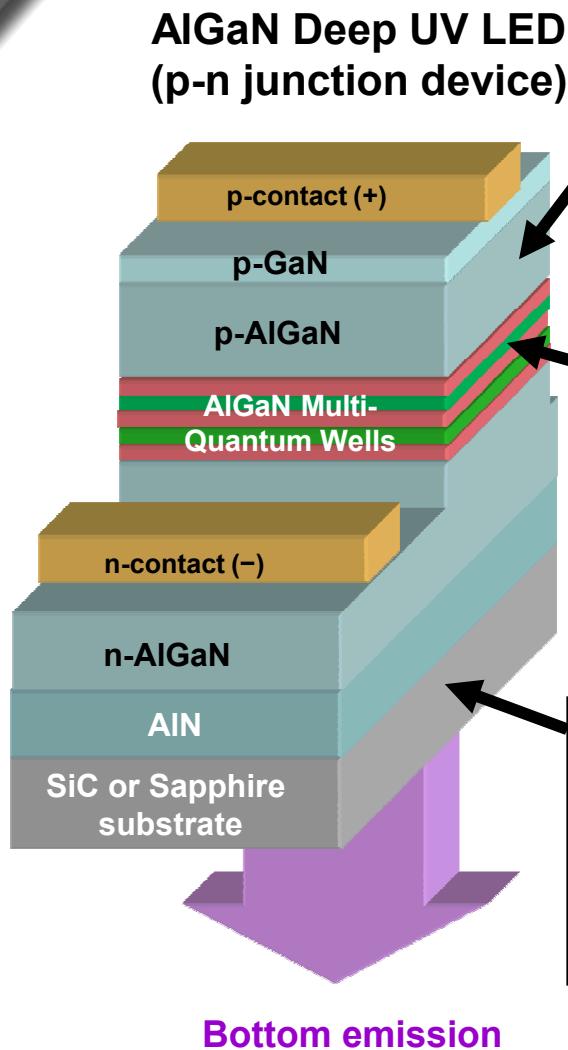
Limitations:

- Present devices only ~2% efficient
- Estimate > 10% efficiency is needed for practical implementation
- Materials breakthroughs needed!

AlGaN Semiconductor System



Materials challenges for realizing high performance AlGaN deep UV LEDs



p-type AlGaN is very difficult

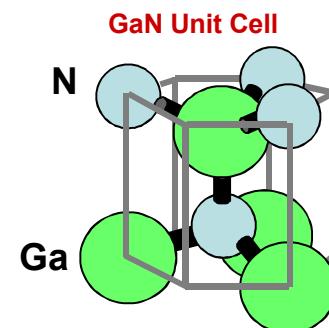
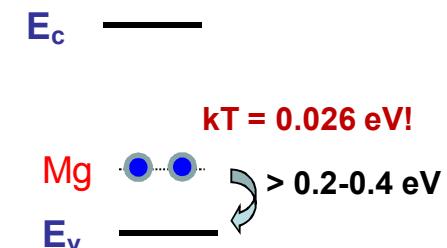
- Large acceptor ionization energies
- Compensating defects
- P-GaN is better, but absorbs deep-UV!

AlGaN Quantum Wells have low optical efficiency

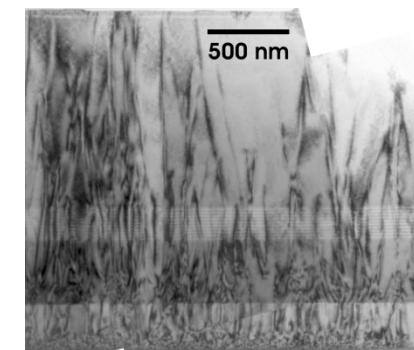
- Non-radiative crystalline defects (e.g., impurities, vacancies)

Lack of AlGaN Substrates

- high densities of extended defects (threading dislocations) $> 10^9 \text{ cm}^{-2}$
- Reduced device efficiency and operational lifetime



TEM image of AlGaN on sapphire



Sapphire substrate

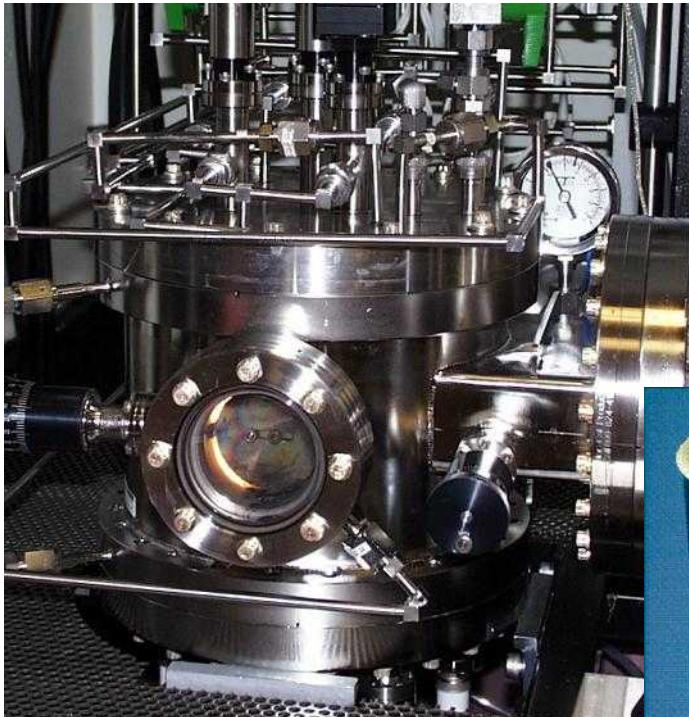


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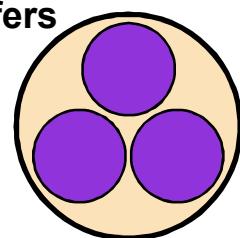


Epitaxial Growth of Nitride Semiconductors by Metal-organic Vapor Phase Epitaxy at Sandia

Veeco D-125 Rotating Disk MOVPE System



3 two-inch wafers



Rotation ~ 1500 rpm

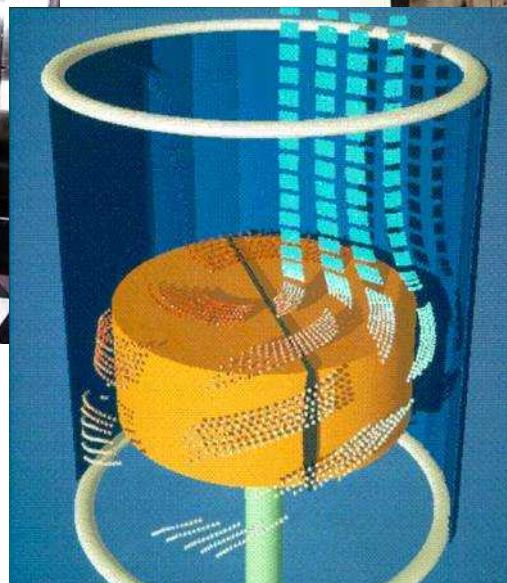
AlGaN Growth

Sources: TMGa, TMAI, NH₃

Temp: 1035-1100°C

Pressure: 75-300 torr

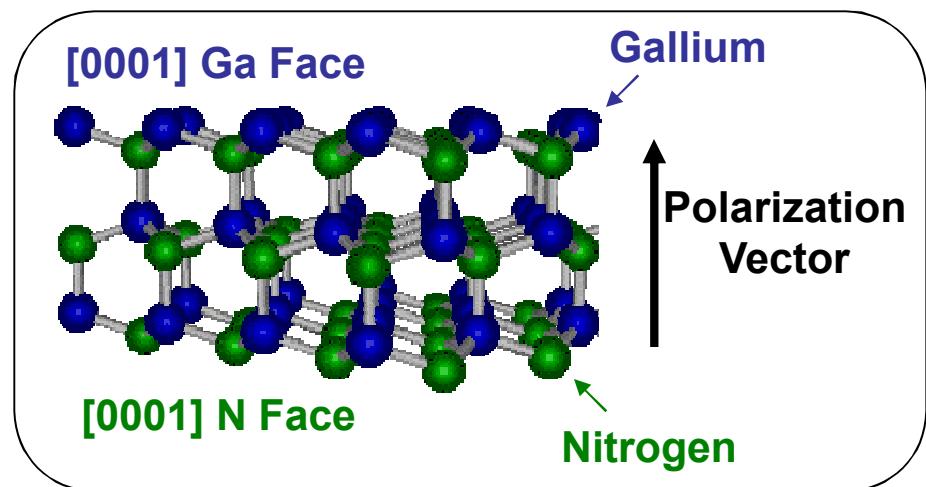
Growth rates: 0.3-1 $\mu\text{m}/\text{hour}$



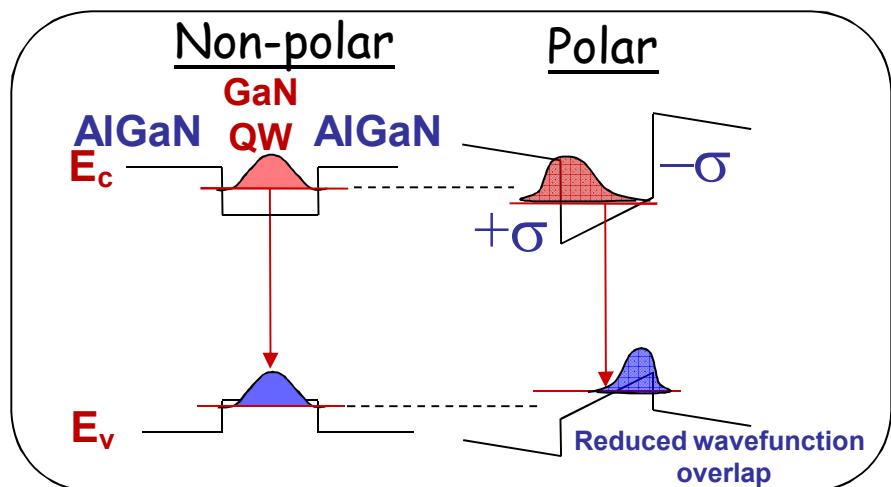
Andrew Allerman,
Org. 01126

Proposed P-type Doping Solution: Mg-doped Short-Period Superlattice

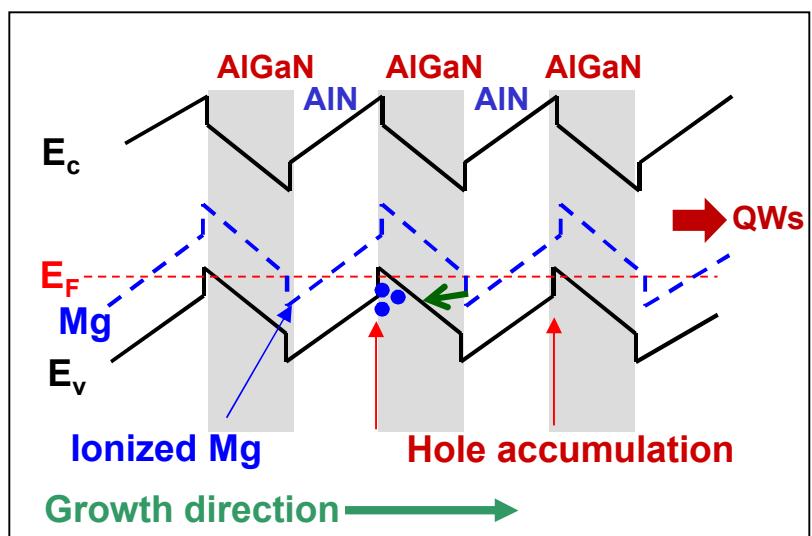
Wurzite GaN crystal structure



Polarization effect on GaN quantum well



Mg-doped Polarization Superlattice

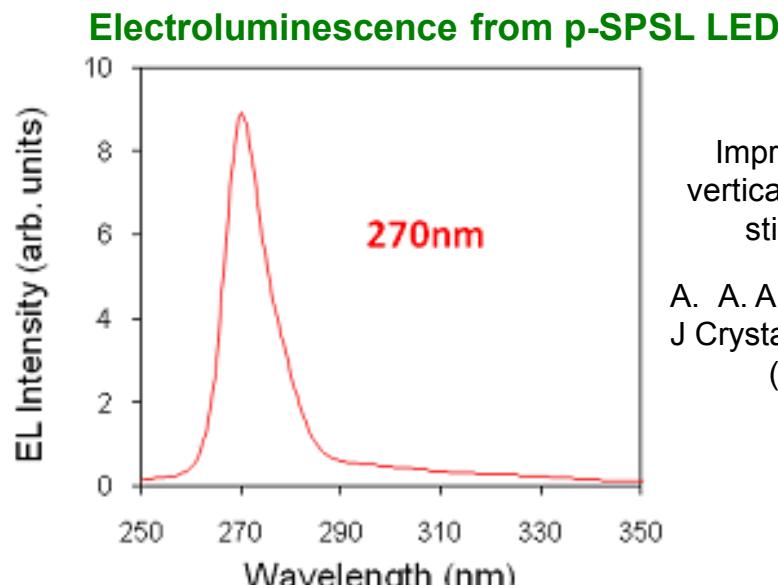
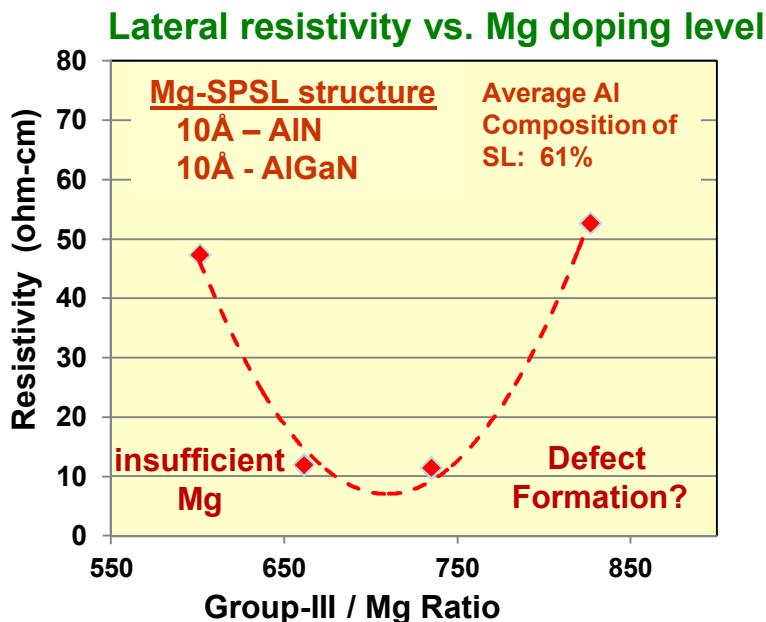
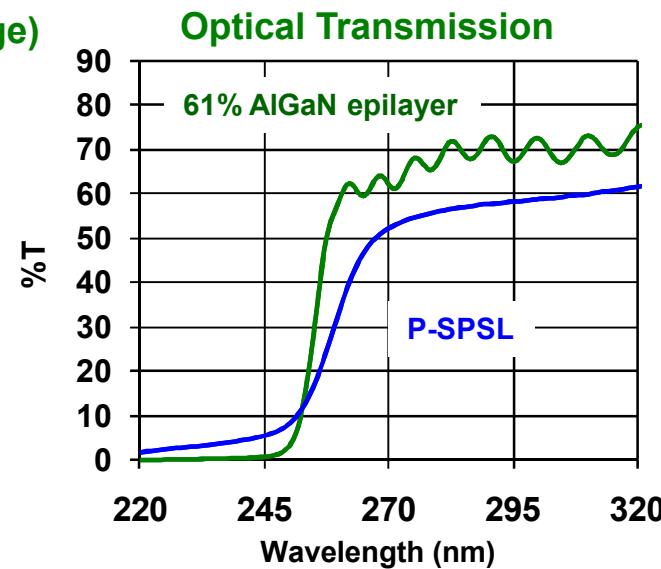
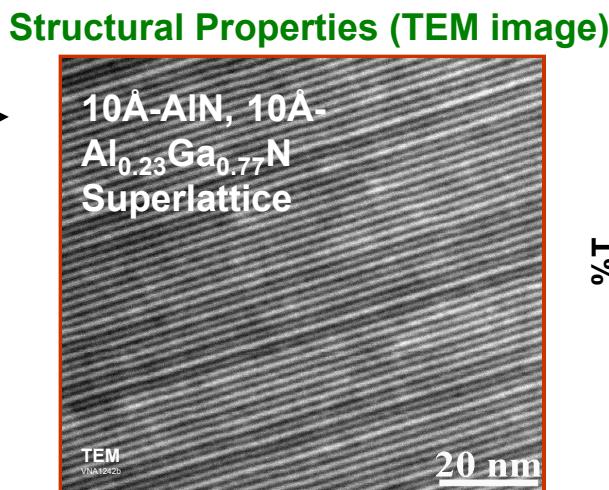
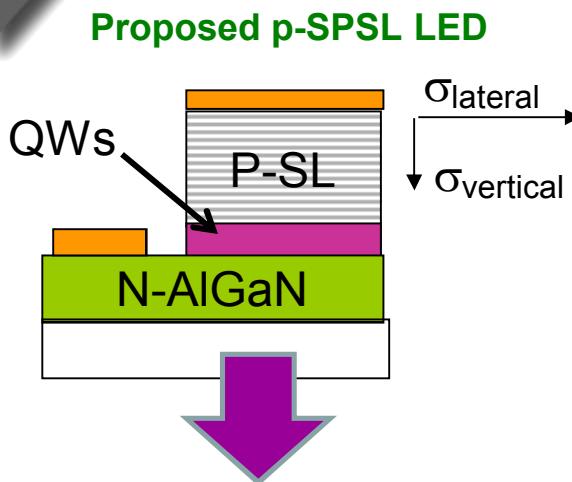


- Manipulation of polarization fields alters electronic states and enables hole accumulation
- Use of “ultrathin” layers (5-15Å) in the SL enables:
 - high effective bandgap of random alloy (Al~0.60)
 - possibility of tunneling-assisted vertical transport

Deep-UV-Transparent
Hole Injector

Nikishin et al
JAP (2005)
(MBE growth)

Progress to Date on Mg-doped SPSLs



Improvement of vertical conductivity still needed

A. A. Allerman et al, J Crystal Growth, (2010)

Application of Novel Tools to Study Point Defects

Motivation

- Point defects (*vacancies, impurities, etc.*) may cause non-radiative recombination, dopant compensation, defect-assisted carrier tunneling from active region

Challenge

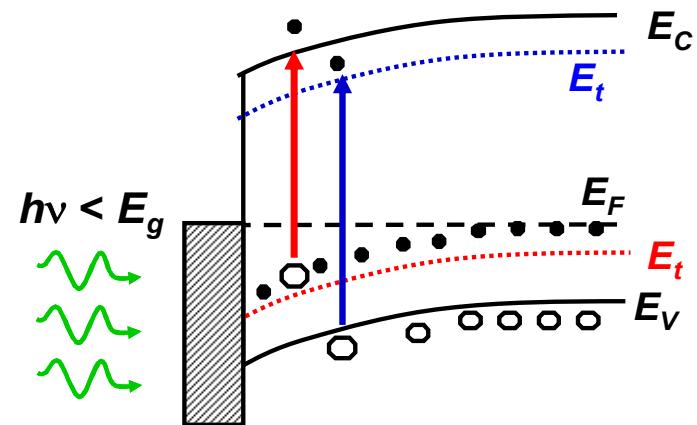
- Most common experimental techniques (e.g., DLTS) can't probe entire bandgap

Deep Level Transient Spectroscopy



- limited to $\sim 1 \text{ eV}$ of E_c, E_v
- cannot probe mid-gap non-radiative centers

Deep Level Optical Spectroscopy



- photo-capacitance technique
- application of tunable light excitation to access entire bandgap

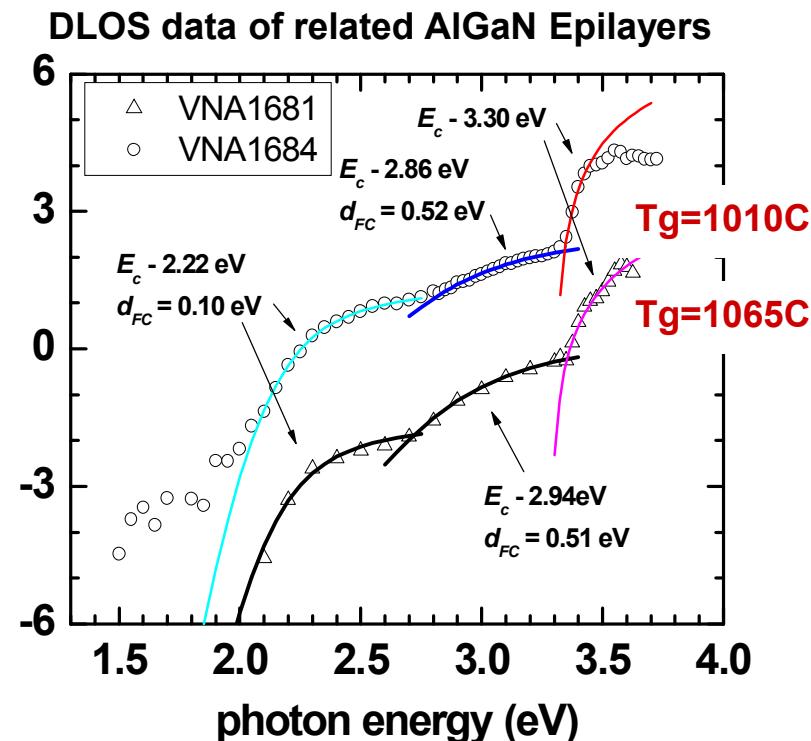
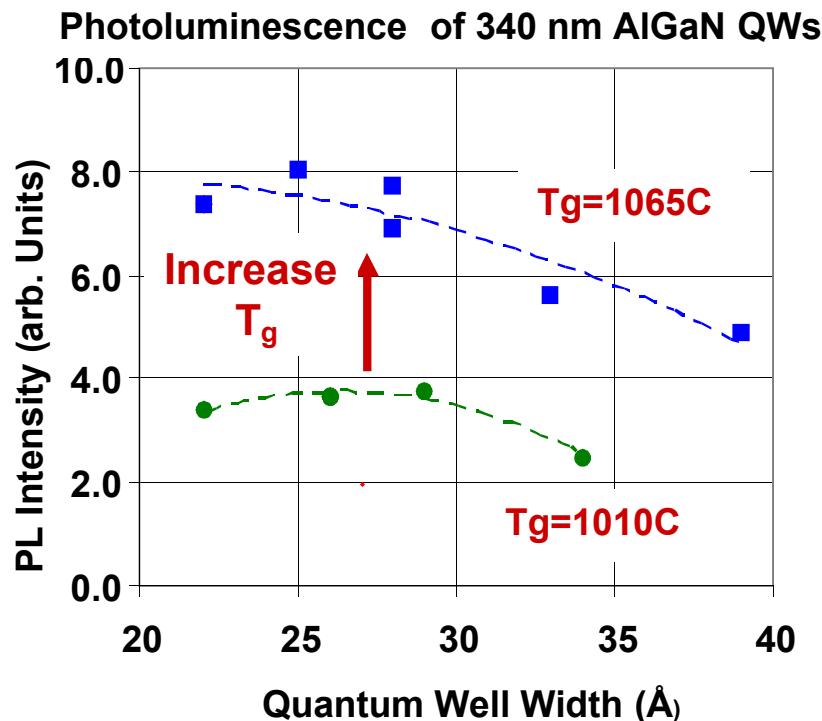
Combination of photoluminescence and DLOS to study impact of QW growth temperature

Materials Growth Conditions

Defect Properties

Materials Performance

Impact of growth temperature on AlGaN quantum well luminescence



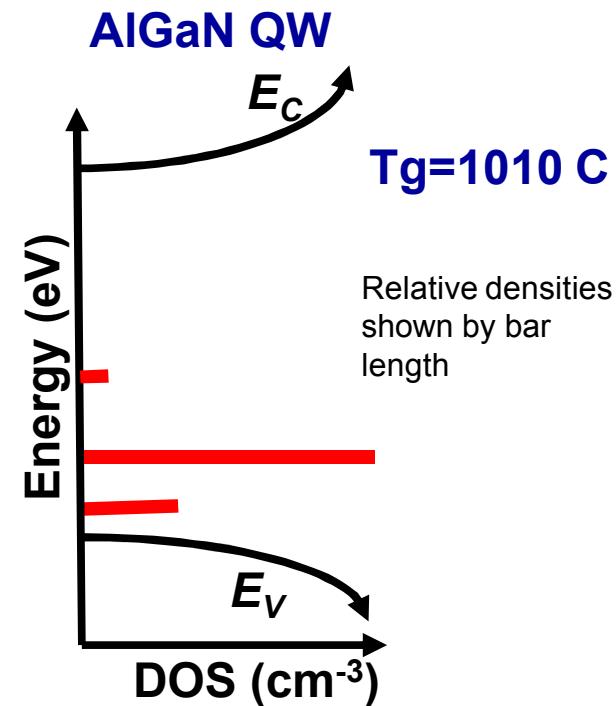
→ Change in growth temp does not introduce new defect levels

Combination of photoluminescence and DLOS to study impact of QW growth temperature

Lighted CV measurements to determine densities of deep levels (cm^{-3})

Trap Energy	T _g 1065°C	T _g 1010°C	Change
E _c -2.22 eV	2.5e15	1.1e16	4.4X
E _c -2.90 eV	2.7e16	9.0e16	3.3X
E _c -3.30 eV	7.7e15	3.0e16	3.8X

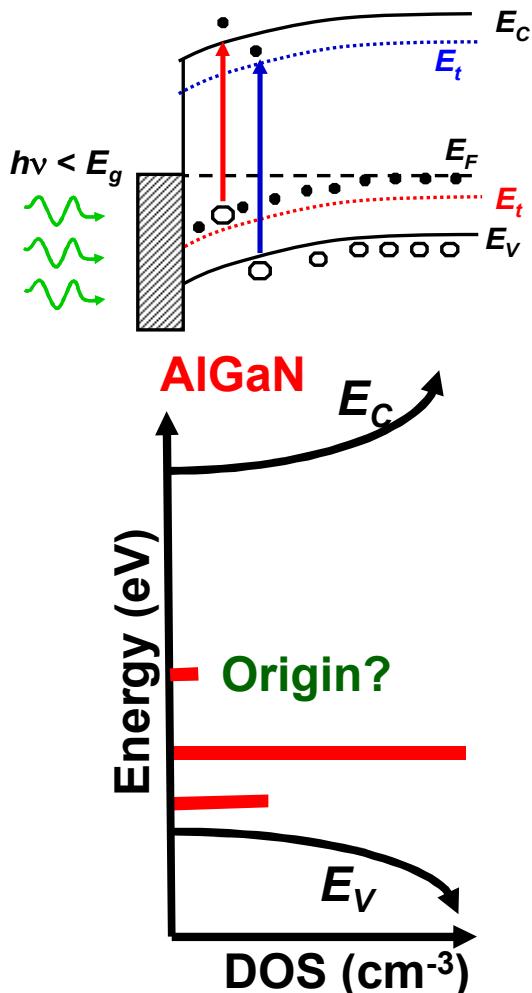
- ~3-4X increase in deep level density across the spectrum with lower T_g
- Increased defect density correlated with ~ 3X decrease in PL deep level intensity



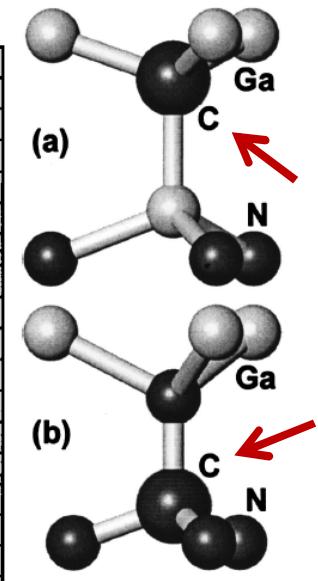
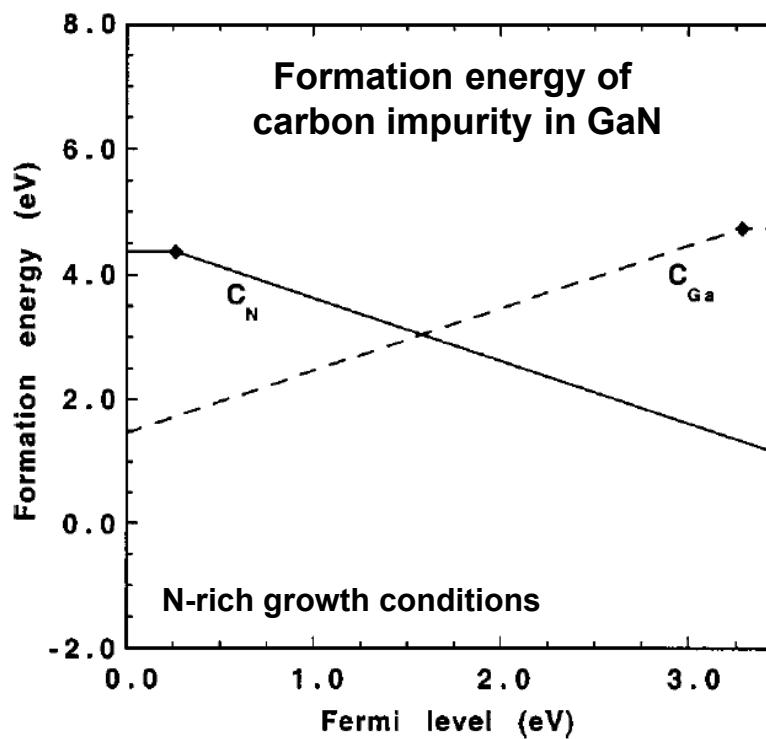
First quantitative correlation of AlGaN growth conditions, increased deep level densities, and lower luminescence intensity

Identification of physical origin of defect levels: Experiment and Theory

Experiment: DLOS



Theory: Density Functional Theory

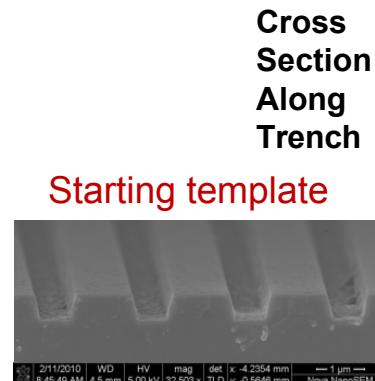
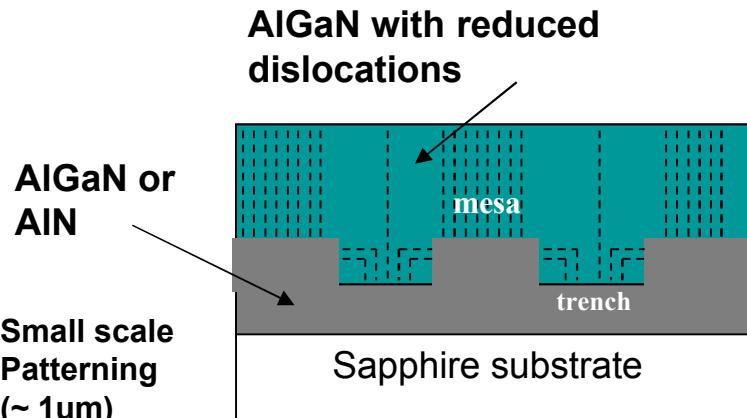


A. F. Wright, JAP 92, 2575 (2002)

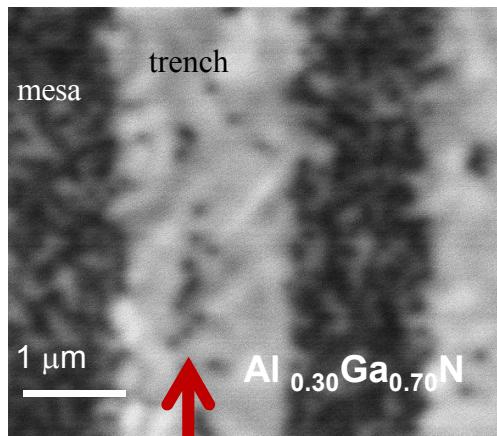
- Formation energies of defects
- Energies of defect levels
- Capture cross-sections

Materials Engineering for Mitigation of Extended Defects

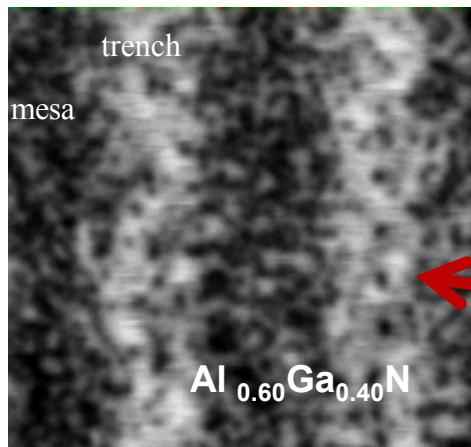
AlGaN Growth on Corrugated Templates



CL of 340 nm AlGaN QWs

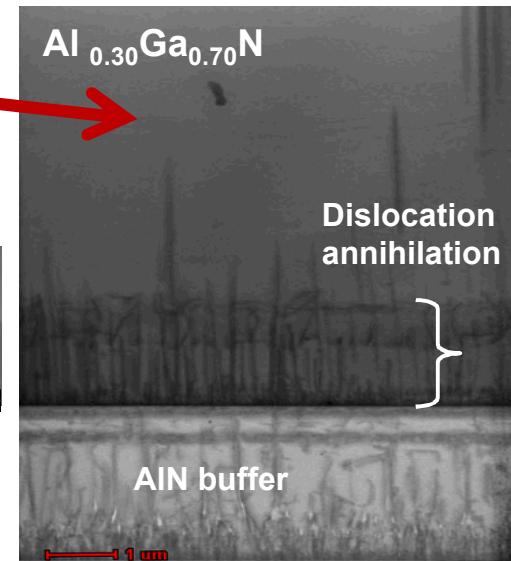


CL of 280 nm AlGaN QWs



• 10-30X TD reduction in $\text{Al}_{0.30}\text{Ga}_{0.70}\text{N}$ (340 nm), to $2-4 \times 10^8 \text{ cm}^{-2}$ in trenches

TEM of AlGaN Epilayer



- Dislocations largely annihilated in ~1.5 microns of growth!

Demonstration of viability in germicidal region (< 300 nm)

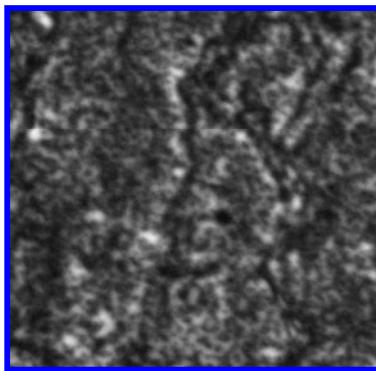
A. Allerman

Iida et al., J. Crystal Growth (2007)
Kueller et al., J. Crystal Growth (2010)

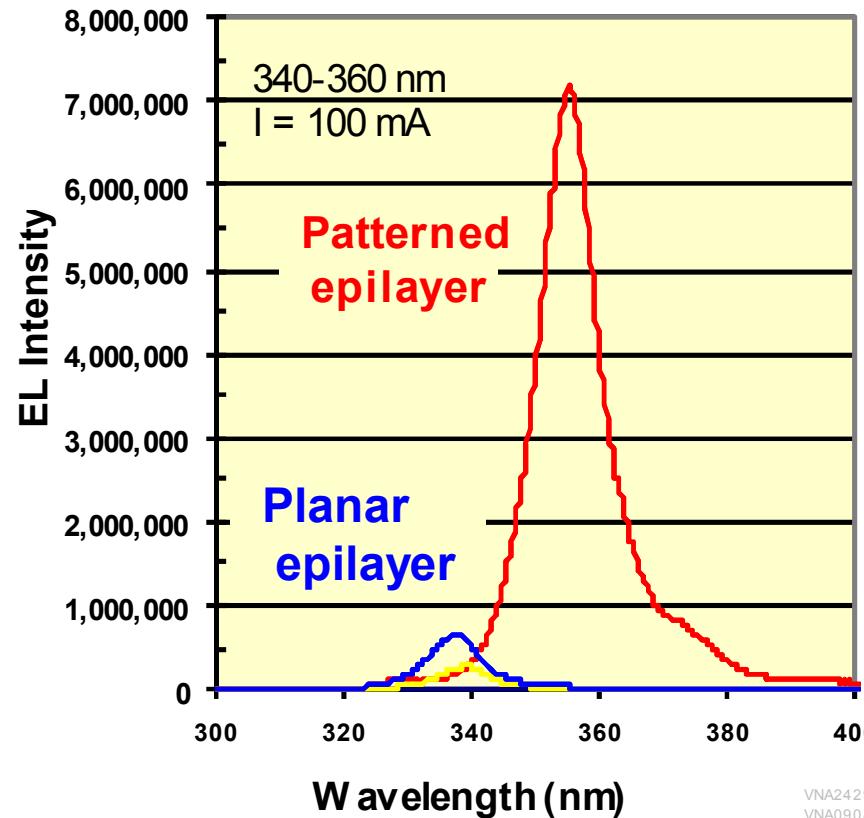
Impact of Dislocation Reduction

Electroluminescence of p-n Junction structure

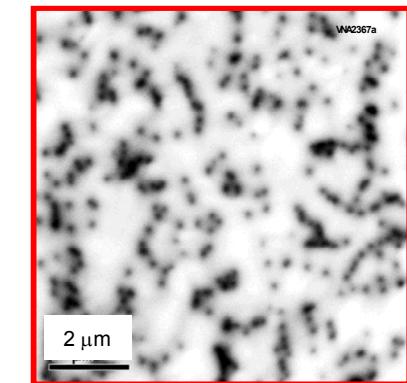
CL from planar AlGaN epilayer



$\text{Al}_{0.30}\text{Ga}_{0.70}\text{N}$
No patterning



CL from patterned AlGaN epilayer



$\text{Al}_{0.30}\text{Ga}_{0.70}\text{N}$

- *10x increase in LED emission with patterned AlGaN template!*
- Improved CL (reduced dislocations) leads to improved EL
- Presently working toward implementation in deeper UV LEDs



Summary

Goal: develop novel UV sources based on LEDs to enable point-of-use water purification systems with enhanced capabilities

- Requires overcoming major materials challenges of AlGaN alloys, including fundamental limitations to p-type doping, and the effects of point and extended defects
- Developed Mg-doped polarization superlattices as a means to circumvent thermal activation of p-type dopants and achieve hole Injection with a deep UV transparent structure; 1st generation LEDs with emission in the germicidal region
- Applied DLOS to achieve new insights into the correlation of AlGaN growth conditions, defect properties, and materials performance; potential to understand and control defect populations
- Advancing patterned-growth defect-reduction approaches to higher Al-content AlGaN devices, relevant to germicidal region of the spectrum